

Supporting Information

Nucleation and Crystal Growth of Organic-Inorganic Lead Halide Perovskites under Different Relative Humidity

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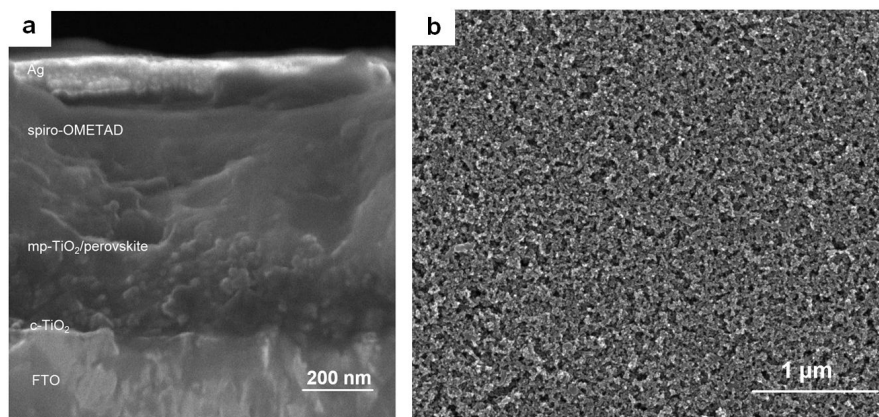


Figure S1. (a) SEM cross-sectional image of $\text{CH}_3\text{NH}_3\text{PbI}_{3-x}\text{Cl}_x$ device. The layers from the bottom are: FTO, c-TiO₂, mp-TiO₂/perovskite, spiro-OMETAD, Ag. (b) SEM image of mp-TiO₂ substrate.

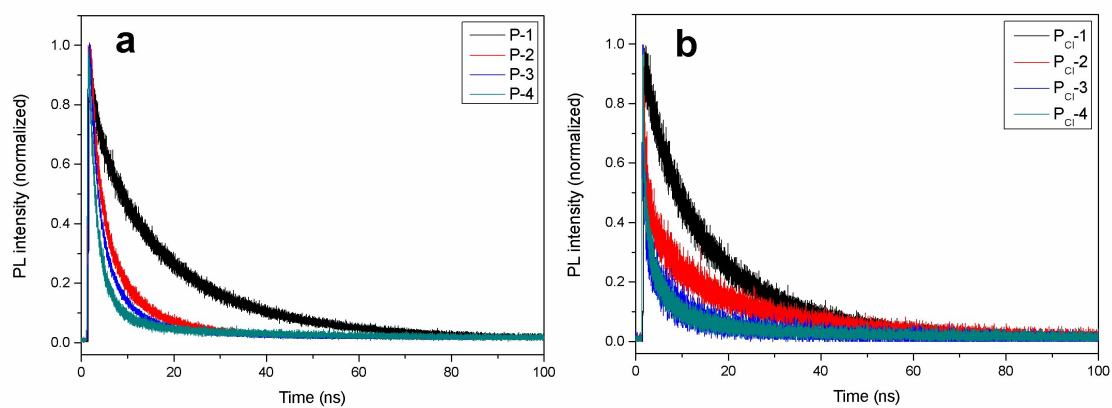


Figure S2. Time-resolved PL decay curves of (a) $\text{CH}_3\text{NH}_3\text{PbI}_3$ and (b) $\text{CH}_3\text{NH}_3\text{PbI}_{3-x}\text{Cl}_x$ films prepared under different humidity conditions.

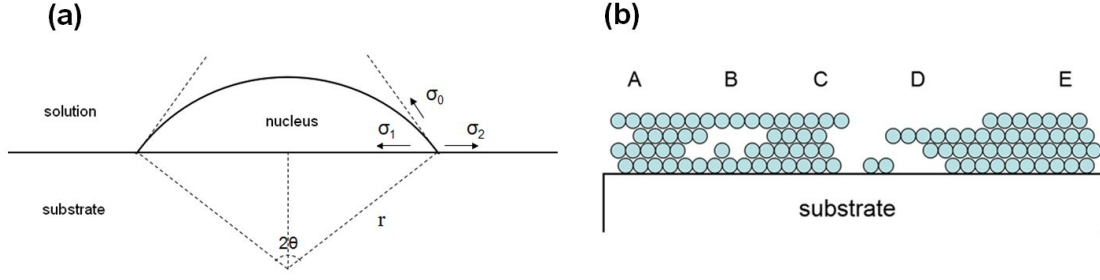


Figure S3. (a) Spherical cap nucleus formed on substrate surface; (b) The difference of supersaturation in different regions (A,C,E > B, D) results in destruction of crystal structure.³

Assuming that spherical cap nucleus is formed on substrate surface (Fig. S3a),¹ we define r as nucleation radius, θ as contact angle of nucleus and substrate, ΔG_v as volume free energy per unit, σ_0 as nucleus surface tension, σ_1 as nucleus and substrate interface tension, σ_2 as substrate surface tension.

Under the equilibrium state, $\sigma_0 \cos \theta = \sigma_2 - \sigma_1$

The change of surface and interface free energy can be expressed as follows:

$$\begin{aligned}\Delta G_s &= 2\pi r^2(1 - \cos \theta)\sigma_0 + \pi(r \sin \theta)^2(\sigma_1 - \sigma_2) \\ &= \pi r^2 \sigma_0 (2 - 3 \cos \theta + \cos^3 \theta)\end{aligned}$$

For the spherical cap nucleus, its volume $V = \frac{\pi r^3(2 - 3 \cos \theta + \cos^3 \theta)}{3}$

So the change of volume free energy

$$\Delta G_v = V \cdot \Delta G_v = \frac{\pi r^3(2 - 3 \cos \theta + \cos^3 \theta)}{3} \Delta G_v$$

The change of total free energy

$$\Delta G = \Delta G_s + \Delta G_v = \pi \left(\frac{r^3}{3} \Delta G_v + r^2 \sigma_0 \right) (2 - 3 \cos \theta + \cos^3 \theta)$$

Set $\frac{\partial(\Delta G)}{\partial r} = 0$, we can conclude the critical nucleus radius:

$$r_0 = \frac{-2\sigma_0}{\Delta G_v} (\Delta G_v < 0)$$

If ΔG_v is seen as the energy needed from equilibrium state to supersaturation, it can be

expressed as $\Delta G_v = -Z(T) \cdot \ln\left(\frac{\rho_s}{\rho_e}\right) = -Z(T) \cdot \ln(\xi + 1)$, in which $Z(T)$ is a temperature

dependent coefficient.¹ So the **critical nucleus radius** can be expressed as

$$r_0 = \frac{2\sigma_0}{Z(T) \ln(\xi + 1)}.$$

The growth type of thin film also depends on the Young's relationship of the interface tensions:²

$$\text{Layer growth} \quad \sigma_2 \geq \sigma_0 + \sigma_1 + \frac{\Delta G_v}{C}$$

$$\text{Island growth} \quad \sigma_2 < \sigma_0 + \sigma_1 + \frac{\Delta G_v}{C}$$

C is a coefficient corresponded to crystal structure. So increased supersaturation is better for layer growth.

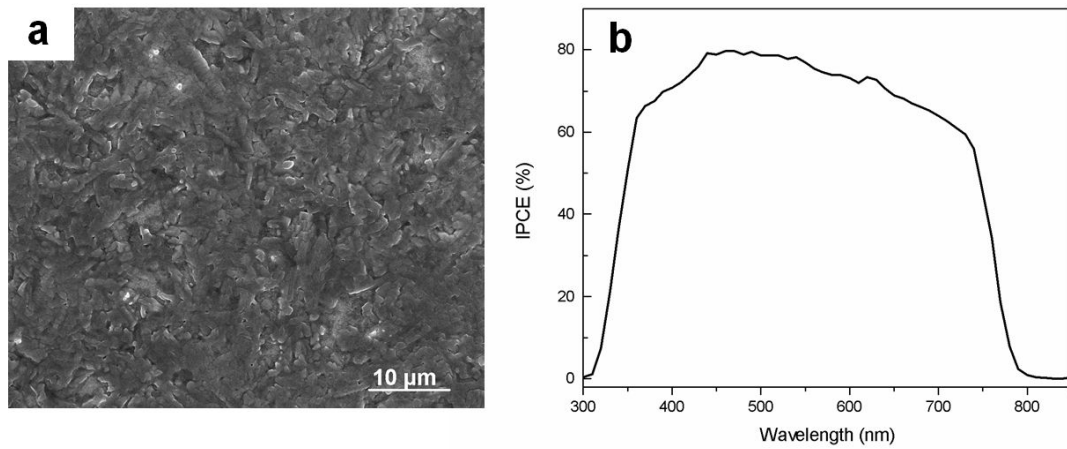


Figure S4. (a) SEM image of $\text{CH}_3\text{NH}_3\text{PbI}_{3-x}\text{Cl}_x$ film spin-coated under RH~10% and annealed under RH~70%. (b) IPCE of the corresponding devices.

Table S1: Photovoltaic parameters measured under AM1.5 illumination of a batch of ten devices based on $\text{CH}_3\text{NH}_3\text{PbI}_{3-x}\text{Cl}_x$ films spin-coated under RH~10% followed by annealing under RH~70%.

Cell	V_{OC} (V)	J_{SC} (mA/cm ²)	FF	PCE (%)
1	0.89	19.1	0.59	10.0
2	0.86	18.7	0.57	9.2
3	0.89	19.6	0.60	10.5
4	0.90	19.5	0.54	9.4
5	0.88	18.5	0.58	9.5
6	0.87	18.6	0.60	9.7
7	0.89	18.9	0.58	9.8
8	0.88	19.8	0.59	10.3
9	0.89	19.5	0.58	10.1
10	0.90	19.1	0.57	9.8
Average	0.88 ± 0.02	19.1 ± 0.6	0.58 ± 0.03	9.9 ± 0.5

References

1. Venables, J. A. *Introduction to Surface and Thin Film Processes*, World Publish Corporation, Beijing, **2003**.
2. Aliofkhazraei, M.; Ali, N. *Two-Dimensional Nanostructure*, CRC Press (an imprint of Taylor & Francis Group), Boca Raton, **2012**
3. Zhang, K. C.; Zhang, L. H. *Crystal Growth (in Chinese)*, Science Press, Beijing, **1981**.